

08 / 08 / 05

SHEET 1 OF 1

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)			ATTY. DOCKET NO. 005916 USA/ FPS/MMCS/MC	SERIAL NO. 09/998,384		
			APPLICANT Young Joseph PAIK			
			FILING DATE November 30, 2001	GROUP 2812 2823		
U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)						
K.N.	Boning, Duane et al. "Run by Run Control of Chemical-Mechanical Polishing." <i>IEEE Trans.</i> October 1996. Vol. 19, No. 4. pp. 307-314.					
K.N.	Moyné, James et al. "A Run-to-Run Control Framework for VLSI Manufacturing." <i>Microelectronic Processing '93 Conference Proceedings.</i> September 1993.					
K.N.	Telfeyan, Roland et al. "Demonstration of a Process-Independent Run-to-Run Controller." <i>187th Meeting of the Electrochemical Society.</i> May 1995.					
K.N.	Moyné, James et al. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Adv. Semiconductor Manufacturing Conference.</i> August 15, 1995.					
K.N.	Moyné, James et al. "Adaptive Extensions to be a Multi-Branch Run-to-Run Controller for Plasma Etching." <i>Journal of Vacuum Science and Technology.</i> 1995.					
K.N.	Sachs, Emanuel et al. "Process Control System for VLSI Fabrication."					
K.N.	Chaudhry, Nauman et al. "Active Controller: Utilizing Active Databases for Implementing Multi-Step Control of Semiconductor Manufacturing." <i>University of Michigan.</i> pp. 1 - 24.					
K.N.	Chaudhry, Nauman et al. "Designing Databases with Fuzzy Data and Rules for Application to Discrete Control." <i>University of Michigan.</i> pp. 1 - 21.					
K.N.	Chaudhry, Nauman A. et al. "A Design Methodology for Databases with Uncertain Data." <i>University of Michigan.</i> pp. 1 - 14.					
K.N.	Khan, Kareemullah et al. "Run-to-Run Control of ITO Deposition Process." <i>University of Michigan.</i> pp. 1 - 6.					
K.N.	Moyné, James et al. "Yield Improvement @ Contact Through Run-to-Run Control."					
K.N.	Kim, Jiyoun et al. "Gradient and Radial Uniformity Control of a CMP Process Utilizing a Pre- and Post-Measurement Strategy." <i>University of Michigan.</i>					
EXAMINER <i>Khemani</i>	DATE CONSIDERED <i>01/20/06</i>					
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. If citation is not in conformance, initial here and attach brief statement.						

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PTO/SB/08a/b (07-05)
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Substitute for form 1449A/B/PTO				Complete if Known	
				Application Number	09/998,384
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				First Named Inventor	Young J. PAIK
				Art Unit	2823
				Examiner Name	K. D. Nguyen
Sheet	1	of	1	Attorney Docket Number	005916 USA/FET/FET/DV

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
K.N.	AA*	US-6,093,080	07-25-2000	Inaba et al.	

FOREIGN PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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NON PATENT LITERATURE DOCUMENTS					
Examiner Initials	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			T ²
K.N.	CA	Office Action dated 07/01/2005 from U.S. Patent Application No. 11/118,711, filed 04/29/2005.			

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Examiner Signature 5349981	K. D. Nguyen	Date Considered	01/20/06
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